

Product sheet

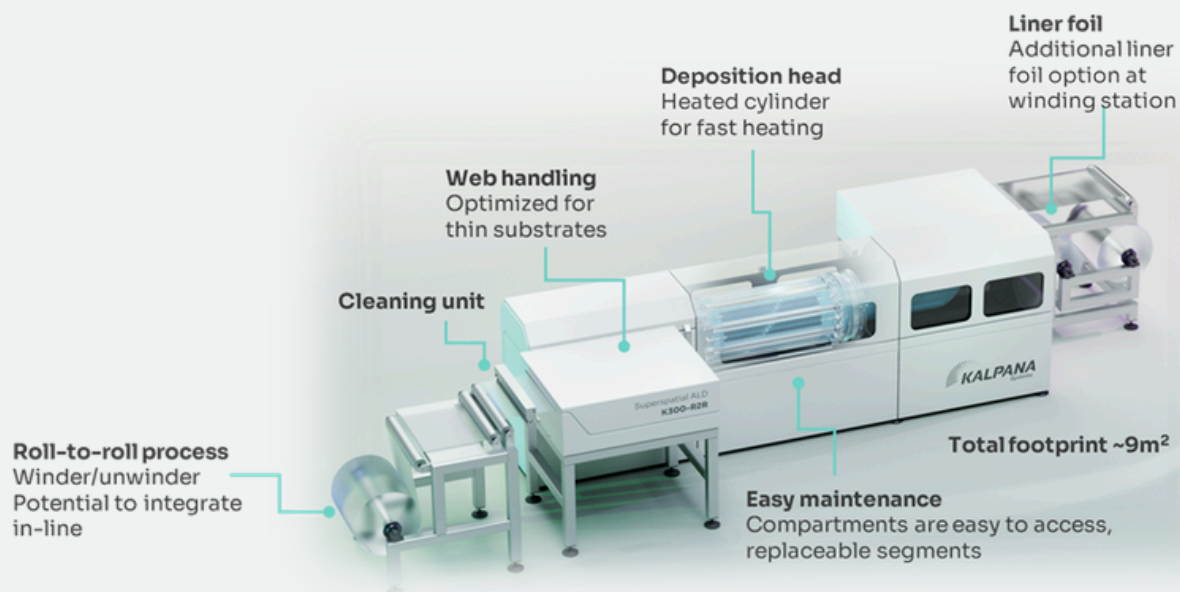
Specifications for
thin film equipment with
Superspatial ALD



Wake up to your imagination

Superspatial ALD is finally here.

Kalpana Systems' revolutionary Superspatial ALD concept makes spatial ALD feasible for industries demanding perfect layers at low cost and high speed.



Endless possibilities

Our Superspatial ALD concept allows for deposition of multiple layers of various materials in one deposition process. Atmospheric pressure enables inline integration, and combinations with other deposition techniques.

Designed for industry

Kalpana Systems' equipment is designed from an industrial point of view:

- High throughput
- High uptime
- Easy maintenance
- Easy integration into existing production lines

Sustainability

Besides enabling new possibilities in sustainable markets such as PV and batteries, using our equipment will result in a small environmental footprint. Our systems operate at/ with:

- Low temperature
- Atmospheric pressure (ALD)
- High precursor utilization

The roll-to-roll spatial ALD equipment can be delivered in two versions: the K300 and the K600.

| Equipment Specifications | K300 | K600 |
|--------------------------|----------------------------------|------------------------------------|
| Web width | 100-600 mm | 600-1500 mm |
| Web speed | 0-10 m/min | |
| Max. ALD process speed | <200 cycles/m ² /min | 200-800 cycles/m ² /min |
| Web materials | PET, PEN, PI, SS, Alu, Cu, Ni... | |
| Process temperature* | 80-150 degrees C | |
| Number of precursors* | 4 | 6 |

*Can be increased on request

The following additional equipment can be delivered as part of the K300 and K600 product offering:

- Gas cabinets
- Scrubber system
- R&D tool for lab scale testing
- Water Vapor Transmission Rate (WVTR) measurement equipment “Ultratrace 6”





Contact

Our product specialists are happy to exchange the possibilities for your ideas or explore the opportunities for a sample or a live demo of our equipment.

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